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**Zhiping Zhou
Changhe Zhou
Pavel Cheben**
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Introduction

The tremendous demand on high-density data communications, real time sensing/detection, and high-speed control/actuation has heated up the research and development in Micro/Nano Photonics, which studies the behavior of light on the micro/nanometer scale and deals with high bandwidth, high speed, and ultra-small optoelectronic components. We are glad to see this subject attracting an increasing amount of attention and interest, with many more summer schools, topical symposiums and conferences in an attempt to promote the study of Micro/Nano Photonics; as well as dedicated peer-reviewed journals such as Photonics Research furthering the frontier of this research field. The joint efforts of academia and industry combined forms the engine of the versatile photonics.

It was in this spirit that the Micro/Nano Photonics and Fabrication conference of OIT' 2015 was organized. The conference accepted over 25 papers from different countries and areas of the world focused on the design, fabrication, and application of micro/nanostructures, and they crossed many research disciplines including: silicon photonics integration, active nanomaterials, metamaterials, nanostructure device, and fabrication technology. We also invited renowned scholars to present their cutting-edge breakthroughs, covering fundamental science such as nonlinear conversion and plasmonic enhancement, and technological advancements involving Germanium platform in mid-infrared applications. These experts and contributors together made a great feast of intellect.

As the committee chairs, we would like to express our appreciation to: the committee members for their support, the presenters for devoting their precious time to write the intriguing articles, and the reviewers for their helpful comments. We are also grateful to the staff of SPIE for their efforts in publishing the volume of this Proceedings.

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